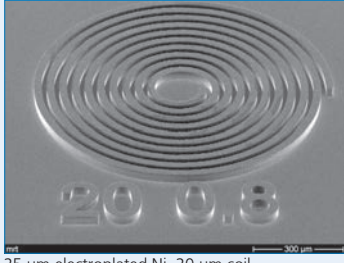
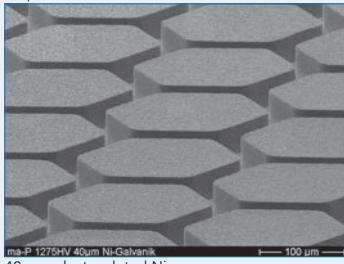
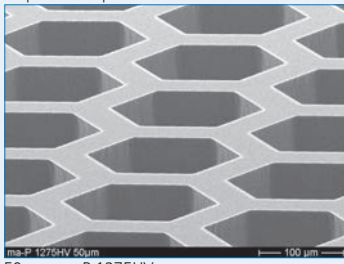
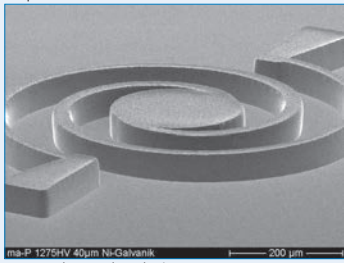
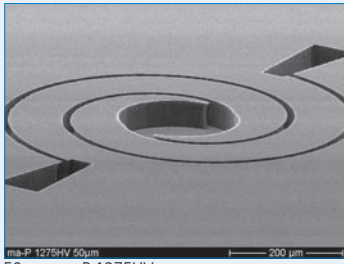


ma-P 1275 and ma-P 1275HV – Positive Tone Photoresists

Versatile high viscosity positive tone photoresists for microsystems technology

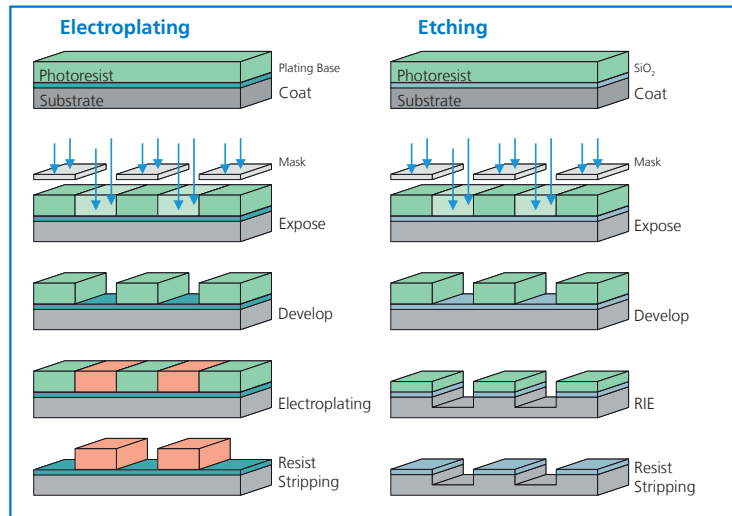


All resist patterns obtained by mask aligner broadband exposure
 11.06.18

Characteristics

- Specifically designed for electroplating of structures in microsystems technology
- High stability in acid and alkaline plating baths
- High dry and wet etch resistance
- Good thermal stability of the resist patterns attainable
- Aqueous alkaline development
- Easy to remove
- Side wall angle up to 87° with mask aligner broadband exposure
- Suitable for pattern reflow

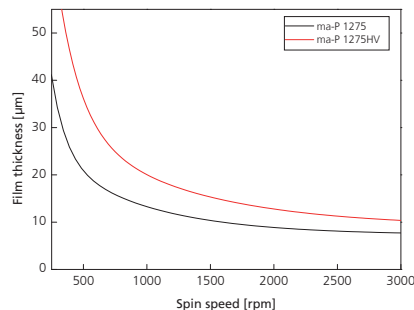
Process flow



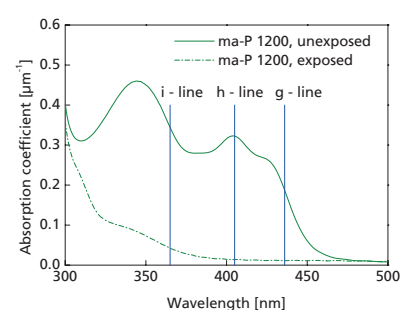
Film thicknesses

Film thickness	µm	7.5	11	20	30	40	50
ma-P 1275	rpm	3000		500	350	250	-
	s	30		60	60	60	
ma-P 1275HV	rpm	-	3000	1000	600	450	400
	s		30	60	60	60	60

Spin curves



UV/vis spectra



Applications

- Mould for electroplating
- Etch mask for metal and semiconductor substrates – e.g. microlenses from reflowed patterns
- Mask for ion implantation
- Mould for UV moulding after reflow

